



DIELECTRIC PROPERTIES OF NIO-BASED CERAMICS

MR. PRASIT THONGBAI

A THESIS FOR THE DEGREE OF DOCTOR OF PHILOSOPHY
KHON KAEN UNIVERSITY
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ในงานวิจัยนี้ได้ศึกษาเพื่อหาจุดกำเนิดของการมีค่าคงที่ใดอิเล็กตริกที่สูงมากของ วัสคุเซรามิก $\text{Li}_x\text{Ti}_x\text{Ni}_{\text{L.x.}}$ O(x=0-0.10 and y=0-0.15) ที่เตรียมโดยวิธีพอร์ลิเมอร์ไลโรไลซีส ได้ศึกษาลักษณะโครงสร้างผลึกโดยใช้เทคนิคการเลี้ยวเบนของรังสีเอกซ์ (XRD) ส่วนการศึกษา โครงสร้างทางจุลภาคใช้กล้องจุลทรรศน์อิเล็กตรอนแบบส่องกราค (SEM) ร่วมกับเครื่องตรวจ วิเคราะห์การกระจายพลังงาน (EDS) และได้ศึกษาสมบัติทางไดอิเล็กตริกและสมบัติทางไฟฟ้าของ วัสคุเซรามิกในช่วงความถี่และอุณหภูมิต่างๆ

ผลการศึกษาโดยใช้เทคนิค XRD และ SEM-EDS ได้แสดงว่า ปริมาณการเจือของ Li และ Ti มีผลกระทบอย่างมากต่อการเกิดเฟสและการเปลี่ยนแปลงของโครงสร้างทางจุลภาคของวัสคุ เซรามิก $\mathrm{Li}_{x}\mathrm{Ti}_{y}\mathrm{Ni}_{1.x.y}\mathrm{O}$ ผลการทคลองพบว่า ไอออนของ Ti^{4+} ที่ใช้ในการเจือมีแนวโน้มที่จะรวมตัว กับ NiO เกิดเป็นเฟสเจือปนของ NiTiO, ในขณะที่ใอออนของ Li⁺ สามารถแทนที่ตำแหน่งใอออน ของ Ni²⁺ในโครงข่ายผลึกได้ และยังสามารถช่วยกระตุ้นให้ใอออนของ Ti⁴⁺ สามารถแทนที่ ์ ตำแหน่งของ Ni²⁺ ใค้เพิ่มมากขึ้น ผลการศึกษาโครงสร้างทางจุลภาคด้วยเทคนิค SEM-EDS ยืนยัน ใค้ว่าอนุภาคของ NiTiO, มีการสะสมอย่างมากที่ขอบเกรนและผิวหน้า อย่างไรก็ตาม เมื่อเพิ่ม ปริมาณการเจือไอออนของ $\operatorname{Li}^{\scriptscriptstyle op}$ อนุภาคของ NiTiO_3 จะไม่ปรากฏในโครงสร้างทางจุลภาค การเปลี่ยนแปลงโครงสร้างทางจุลภาคดังกล่าวนี้สามารถอธิบายได้โดยใช้กลไกการเผาผนึกแบบ เฟสของเหลว จากการศึกษาสมบัติทางใดอิเล็กตริกพบว่า วัสดุเซรามิก $\operatorname{Li}_{_{x}}\operatorname{Ti}_{_{y}}\operatorname{O}$ มีค่า คงที่ใดอิเล็กตริกที่สูงมาก โดยมีค่าประมาณ 10^3 - 10^5 และพบว่าค่าคงที่ใดอิเล็กตริกมีค่าเพิ่มตาม ขนาคของเกรนที่เพิ่มขึ้น กระบวนการผ่อนคลายทางใคอิเล็กตริกที่ความถี่ต่ำ (LFR) และที่ความถี่ สูง (HFR) สามารถเกิดขึ้นได้ในวัสดุเซรามิกที่มีปริมาณการเจือไอออนของ ${
m Ti}^{4+}$ ที่สูง แต่ปริมาณ ใกลอนของ Li⁺ต่ำ ทั้งกระบวนการ LFR และ HFR สามารถอธิบายได้โดยการประยุกต์แบบจำลอง การผ่อนคลายทางใดอิเล็กตริก Cole-Cole ร่วมกับพจน์ของการนำไฟฟ้ากระแสตรง ผลการศึกษา อิทธิพลของชั้นผิวหน้าของวัสคุเซรามิก Li,Ti,Ni,x,O พบว่าการขัดผิวหน้าของวัสคุเซรามิก ใค้ส่งผลต่อกระบวนการ LFR แต่ไม่ส่งผลต่อ HFR จากผลการศึกษาด้วยเทคนิคอิมพีแคนซ์สามารถ พิสูจน์ได้ว่า ชั้นผิวหน้าที่เกิดจากการสะสมของ NiTiO_3 มีสมบัติทางไฟฟ้าเป็นฉนวนและส่งผล ต่อเนื่องถึงสมบัติทางใคอิเล็กตริกที่ความถี่ต่ำ เมื่อขัดชั้นฉนวนของผิวหน้าออก ค่าคงที่ใคอิเล็กตริก

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จะมีค่าลดลง แต่ค่าการสูญเสียทาง ไดอิเล็กตริกมีค่าเพิ่มขึ้น นอกจากนี้แล้วยังพบว่า ปริมาณของ ช่องว่างออกซิเจนในโครงสร้างมีผลอย่างมากต่อกระบวนการ LFR และ HFR หลังจากกระบวนการ อบให้ความร้อนภายใต้บรรยากาศอาร์กอนเพื่อเพิ่มปริมาณช่องว่างของออกซิเจนพบว่า ความ ต้านทานรวมและความต้านทานของเกรนมีค่าเพิ่มมากขึ้น การเปลี่ยนแปลงค่าความต้านทาน ดังกล่าวนี้ได้ส่งผลต่อเนื่องถึงสมบัติทางไดอิเล็กตริกของวัสดุเซรามิกตัวอย่างเป็นอย่างมากทั้ง ในช่วงกระบวนการของ LFR และ HFR จากการศึกษาผลของชั้นฉนวนที่ผิวหน้าและการอบ ให้ความร้อนภายใต้บรรยากาศอาร์กอน แบบจำลองโครงสร้างทางจุลภาคได้ถูกสร้างขึ้นโดยอาศัย พื้นฐานของการโพลาไรเซชันที่ชั้นฉนวนภายในเพื่ออธิบายสมบัติทางไดอิเล็กตริกของวัสดุเซรามิก Li,Ti,Ni...,O

นอกเหนือจากการศึกษาเพื่อหาจุดเริ่มด้นของการมีค่าคงที่ใดอิเล็กตริกที่สูงมากของวัสดุ เซรามิก Li,Ti,Ni,,O แล้ว ในงานวิจัยนี้ยังได้ศึกษาสมบัติทางไดอิเล็กตริกของวัสดุเซรามิก Li,Ti,Ni,,O ที่เครียมโดยวิธีอื่นๆ และวัสดุเซรามิก NiO กลุ่มอื่นๆ คือ Li,V,Ni,,O Li,Fe,Ni,,O และ Li,Al,Ni,,O ผลการทดลองพบว่า ค่าคงที่ใดอิเล็กตริกที่สูงมากของวัสดุเซรามิกกลุ่มดังกล่าว นี้สามารถอธิบายได้โดยใช้พื้นฐานของการโพลาไรเซชันที่ชั้นฉนวนภายในที่เกิดขึ้นในวัสดุเซรามิก ที่มีโครงสร้างทางจุลภาคไม่สม่ำเสมอ ในงานวิจัยนี้ยังได้เปรียบเทียบสมบัติทางไดอิเล็กตริกของ วัสดุเซรามิก Li,O,STi,O,O,Ni,O,O กับวัสดุเซรามิก CuO บริสุทธิ์ ซึ่งเป็นวัสดุที่มีค่าคงที่ใดอิเล็กตริกที่สูงมากเหมือนกับวัสดุเซรามิกกลุ่ม NiO ต่างๆ โดยค่าคงที่ไดอิเล็กตริกที่สูงมากไม่เกี่ยวข้องสารเจือ ใดๆ พฤติกรรมทางไดอิเล็กตริกของวัสดุเซรามิก CuO สามารถอธิบายได้โดยใช้แบบจำลองการ ผ่อนคลายทางไดอิเล็กตริกของ Cole-Cole นอกจากนี้ยังพบว่า ค่าคงที่ใดอิเล็กตริกมีค่าเพิ่มมากขึ้น ตามขนาดของเกรนซึ่งเป็นลักษณะที่บ่งชี้ถึงการเกิดปรากฏการณ์ตัวเก็บประจุแบบชั้นขวางกั้น ภายในในโครงสร้างทางจุลภาคของวัสดุเซรามิก CuO

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ABSTRACT

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In this research, the origin of the giant dielectric response in $\text{Li}_x\text{Ti}_y\text{Ni}_{1-x-y}\text{O}$ ceramics (x = 0-0.10 and y = 0-0.15) prepared by a polymer pyrolysis method is investigated. X-ray diffraction (XRD) and scanning electron microscopy (SEM) with energy dispersive x-ray spectrometer (EDS) are used to characterize the phase composition and microstructure, respectively. The dielectric and electrical properties are investigated as functions of frequency and temperature.

The XRD and SEM-DES results demonstrate that the Li and Ti doping concentrations have remarkable influences on both of the phase formation and microstructural evolution of the Li_xTi_yNi_{1-x-y}O ceramics. It is found that the Ti⁴⁺ ions prefer to form the second phase of NiTiO₃ phase; in contrast, the Li⁺ ions prefer to substitute the Ni²⁺ sites in the NiO crystal lattice. Interestingly, Li doping has a large contribution to the substitution of the Ti⁴⁺ ions on the Ni²⁺ sites. The surface morphologies and microstructure are found to be depended strongly on the Li and Ti doping concentrations. The SEM-EDS results show that the NiTiO3 particles largely accumulate along the grain boundaries and surfaces. Surprisingly, such large accumulation can be erased by increasing the Li doping concentration. The microstructural evolution can suitably be ascribed based on the liquid-phase sintering mechanism. For the dielectric properties, it is revealed that all of the Li_xTi_yNi_{1-x-y}O ceramics exhibit the giant dielectric constant, $\epsilon' \sim 10^3$ - 10^5 . ϵ' of each ceramic composition increases with increasing the grain size. Two sets of relaxations are observed in the dielectric spectra of samples with high-Ti content and relative low-Li content. A low-frequency dielectric relaxation (LFR) is changed with the polishing surface; whereas, a high-frequency relaxation (HFR) remains constant. It can be proved that the NiTiO3 surface layers behave as insulating layers, affecting to the LFR properties—ε' decreases with removing the insulating surfaces accompanied by the increase in loss tangent. Both of the LFR and HFR can be well fitted by the Cole-Cole relaxation equation combined with the dc conduction term. It is found that the oxygen vacancies show a great influence on both of the LFR and HFR processes. The resistance of the grain of all samples increases with annealing of the samples in Ar. The total resistance of the group of samples that exhibit the LFR is found to be enhanced by the annealing. These changes in the resistances can cause a dramatic change in the dielectric properties in both the LFR and HFR processes. According to the investigation of the surface and annealing effects, two suitably models of the microstructure are proposed based on the interfacial polarization mechanism in order to describe the observed giant dielectric response in the Li_xTi_yNi_{1-x-y}O ceramics.

Besides the investigation of the origin of the giant dielectric properties of the Li_xTi_yNi_{1-x-y}O ceramics, the Li_xTi_yNi_{1-x-y}O ceramics with different preparation methods and other NiO-based systems, i.e., (Li, Fe)-, (Li, V)-, and (Li, Al)-doped NiO systems, are also studied in this research. The giant dielectric properties of these ceramic systems can be ascribed based on the interfacial polarization mechanism, resulting from the inhomogeneous structure. Finally, the giant dielectric constant observed in the Li_{0.05}Ti_{0.02}Ni_{0.93}O ceramic is compared to that observed in pure-CuO ceramic. Interestingly, the CuO ceramic can exhibit the giant dielectric properties without any dopants. Moreover, the dielectric relaxation behavior of the CuO ceramic can be ascribed by the Cole-Cole relaxation model just like the Li_{0.05}Ti_{0.02}Ni_{0.93}O ceramic. Furthermore, it is found that the dielectric constant increases with increasing the grain size, suggesting to the internal barrier layer capacitor effect.

Goodness portion of the present thesis is dedicated for my family and all of my teachers

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LIST OF SYMBOLS

σ_{s0}'	Surface charge density
$ec{E}$	Electric filed
$\boldsymbol{\mathcal{E}}_0$	The permittivity of free space (8.854×10 ⁻¹² Fm ⁻¹)
$\mu_{\scriptscriptstyle 0}$	The vacuum permeability
c_{0}	The speed of light in vacuum
\mathcal{E}_{permit}	The permittivity of a dielectric material
ε'	The dielectric constant
C_{0}	The capacitance of the free-space capacitor
C	The capacitance
$ar{\mu}$	The electric dipole moment
$\pm Q$	The electric charges
$ec{P}$	The polarization
N_{\cdot}	The number of the displaced molecules per unit volume
σ_b'	The bound charge density
I_c	The charging current
V	The sinusoidal voltage $(V = V_0 \exp(j\omega t))$
G	The conductance
I_{total}	The total current
I_{I}	The loss current
δ	The loss angle
ε^*	The complex dielectric constant
ε'	The real part of ε^* (the dielectric constant)
ε''	The imaginary part of ε^* (the dielectric loss)
ω tan δ	The angular frequency The loss tangent or the dissipation factor
\vec{D}	The total electric displacement field
	The complex permittivity of a dielectric material
\mathcal{E}_{permit}^{*}	The electric susceptibility
X	The number of dipoles of type i per unit volume
N_i	The average dipole moment
$\overline{\mu}_{\scriptscriptstyle i}$	
α	The polarizability
E'	The local electric field
E_a	The external applied field
$\alpha_{_e}$	The electronic polarizability
α_a	The atomic polarizability
$lpha_{\it or}$	The orientational polarizability

LIST OF SYMBOLS (Cont.)

α_{sc}	The space charge polarizability
P _{total}	The total polarization
P_e	The electronic polarization
P_a	The atomic polarization
P_{or}	The orientational polarization
P_{∞}	The high-frequency polarization
$arepsilon_{\infty}'$	The dielectric constant at a high frequency range
ε_s'	The low-frequency dielectric constant or the relaxed
	static dielectric constant
τ .	The relaxation time
P'	The probability of a jump The valence of the ion
Z P	The zero-frequency value of the hopping polarization
$P_{s(hopping)}$	The Boltzmann constant $(1.38 \times 10^{-23} \text{ J/K})$
$oldsymbol{k}_{B}$	The absolute temperature (K)
b	The distance separating the potential well
α	The Cole-Cole constant parameter ($0 < \alpha \le 1$)
$J_{\scriptscriptstyle total}$	The total current density
J	The conduction current or current density
$oldsymbol{\sigma}_{dc}$	The dc electrical conductivity
σ_{ac}	The ac electrical conductivity
Y^*	The complex admittance
E_a	The activation energy
$f_{p(\varepsilon'')}$	The frequencies at the peak of ε''
$f_{p(\delta)}$	The frequencies at the peak of $ an \delta$
Z^*	The complex impedance
Z'	The real part of the complex impedance The imaginary part of the complex impedance
Z''	The resistances of grains and grain boundaries,
(K_g, K_{gb})	respectively
(C_g, C_{gb})	The capacitances of grains and grain boundaries,
	respectively
${m \mathcal{E}}_{gb}'$	The dielectric constant of the grain boundary
d_g	The grain size
d_{gb}	The thickness of grain boundary
σ	The polaron conductivity

LIST OF SYMBOLS (Cont.)

E_g	The activation energy for conduction inside grain
E_{gb}	The activation energy for conduction at grain boundary
$Ti_{Ni}^{\bullet \bullet}$	The Ti ion sitting on the Ni lattice site with two positive
	charges
V_{Ni}''	The Ni vacancy with double negative charge
$\boldsymbol{arepsilon}_{g}^{*}$	The complex dielectric permittivity of grain
$oldsymbol{arepsilon}_{gb}^{*}$	The complex dielectric permittivity of grain boundary
$Ta_{Ni}^{\bullet \bullet \bullet}$	The Ta ion sitting on the Ni lattice site with three
	positive charges
Li'_{Ni}	The Li ion sitting on the Ni lattice with a single
	negative charge
$V_O^{\bullet \bullet}$	The oxygen vacancy with double positive charges
$[V_O^{\bullet \bullet}]$	The concentration of oxygen vacancy
$Ni_i^{\bullet \bullet}$	The Ni ion in the interstitial lattice site
K	The equilibrium constant
X	The reactance
G	The conductance
B	The susceptance
D	The dissipation factor
R	The resistance
C_p	The capacitance of the parallel plate capacitor
F	The structure factor
f	The atomic scattering factor
D	The diffusion coefficient or diffusivity
$G_{\scriptscriptstyle L}$	The limiting grain size
r	The radius of the including particles
C_s	The capacitance of surface layer
R_{s}	The resistance of surface layer
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